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(54) PHOTOSENSITIVE COMPOSITION FOR VOLUME-PHASE TYPE HOLOGRAM AND RECORDING MEDIUM FOR HOLOGRAM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a photosensitive composition for volume-phase type hologram with which dry development is enabled, it is not necessary to be sealed between cover films or glass substrates on the upper layer of photosensitive layers and transparency, weather resistance, sensitivity, diffraction efficiency and regenerative waveform reproducibility can be improved and a recording medium for hologram.

SOLUTION: This photosensitive composition for volume-phase type hologram is composed of a resin A which is solvent-soluble and becomes a solid on the conditions of ordinary temperature and ordinary pressure, cationic polymerizable monomer B which is a liquid on the condition of normal temperature and pressure, has a boiling point not lower than 100°C under normal pressure and further has a refractive index different from that of the resin A, photopolymerization initiator C for activating cationic polymerization when exposed to active rays, and sensitizing dye D having an amino group for sensitizing the photopolymerization initiator C.

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